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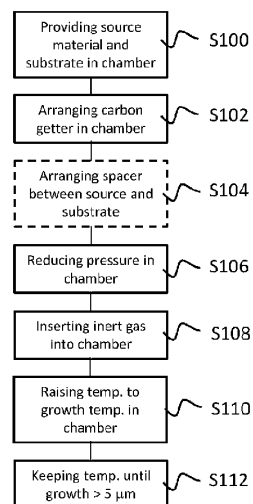
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(54) Title: METHOD OF GROWING HIGH-QUALITY SINGLE CRYSTAL SILICON CARBIDE

Fig. 7



(57) Abstract: A method is disclosed of growing an epitaxial layer on a substrate (20) of monocrystalline Silicon Carbide, SiC. The method comprises providing (S100) a source material (10) of monolithic polycrystalline SiC with a columnar micro-grain structure and the substrate (20) of monocrystalline SiC, in a chamber (5) of a crucible with a distance therein between, arranging (S102) a carbon getter (1) in said chamber (5) of the crucible close to the source material (10) and the substrate (20), said carbon getter (1) having a melting point higher than 2200° C and an ability of forming a carbide layer with carbon species evaporated from SiC, reducing (S106) pressure in the chamber (5), inserting (S108) an inert gas into the chamber (5), raising (S110) the temperature in the chamber (5) to a growth temperature, such that a growth rate between 1 μm/h and 1 mm/h, is achieved, and keeping (S112) the growth temperature until a growth of at least 5 μm has been accomplished on the substrate (20).

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